

	Hits	Search Text	DBs
38	16	(((resist or photoresist or photosensitive or (radiation near5 sensitive)) near16 (mask or pattern\$4 or opening) near24 (strip\$4 or etch\$4 or (dry near5 etch\$4) or RIE or ash\$4 or mill\$4 or (ion near9 beam near4 etch\$4) or plasma)) same (shrink\$4 or reduc\$4 or remov\$4 or etch\$4 or strip\$4) same (sidewall or surface or profile or via or trench or pattern or mask or residu\$3 or side\$3surface or top\$4surface) same (((sulfur near2 oxide) or (sul\$3ur near2 \$2oxide) or ("SO.sub.2") or (sul\$2ur near9 containing)) near28 (Ne or Ar or Xe or Kr or "N.sub.2" or nitrogen or neon or argon or xenon or krypton or "CO" or "CO.sub.2" or (carbon near9 dioxide) or (carbon near9 \$4oxide)))) and (substrate or wafer or platen or device) same (underlayer or underlying or (bottom near9 layer)) same (antireflect\$4 or (organic near9 antireflect\$4 or (organic near9 ARC) or ARC or BARC) same (expos\$4 or reveal or etch\$4 or develop\$4) same (larger or smaller or small or large or width) same (opening or surface or area or region))	US-PGPUB; USPAT; FPRS; EPO; JPO; DERWENT; IBM_TDB

	Hits	Search Text	DBs
39	10	(((resist or photoresist or photosensitive or (radiation near5 sensitive)) near16 (mask or pattern\$4 or opening) near24 (strip\$4 or etch\$4 or (dry near5 etch\$4) or RIE or ash\$4 or mill\$4 or (ion near9 beam near4 etch\$4) or plasma)) same (((sulfur near2 oxide) or (sul\$3ur near2 \$2oxide) or ("SO.sub.2") or (sul\$2ur near9 containing)) near28 (Ne or Ar or Xe or Kr or "N.sub.2" or nitrogen or neon or argon or xenon or krypton or "CO" or "CO.sub.2" or (carbon near9 dioxide) or (carbon near9 \$4oxide)))) and ((substrate or wafer or platen or device) same ((resist or photoresist) near26 pattern\$4 near38 (shrink\$4 or etch\$4 or taper\$4 or reduc\$5 or decreas\$4) near19 (width or area or depth or sidewall or side\$6surface)) same (underlayer or underlying or (bottom near9 layer) or antireflect\$4 or (organic near9 antireflect\$4) or (organic near9 ARC) or ARC or BARC or etch\$4resistant) same (larger or smaller or small or large or width))	US-PGPUB; USPAT; FPRS; EPO; JPO; DERWENT; IBM_TDB